

	Type	Hits	Search Text
1	BRS	24	las r and substrate and (epitaxial adj2 layer\$2) and aperture and (dielectric adj2 mirror)
2	BRS	0	skogman-richard.in.
3	BRS	24	skogman.in.

	<b>DBs</b>	<b>Time Stamp</b>	<b>Comments</b>	<b>Error Definition</b>
<b>1</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/23 13:11</b>		
<b>2</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/23 13:11</b>		
<b>3</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/23 13:11</b>		

	Type	Hits	S arch Text
1	BRS	27	laser and substrate and ( epitaxial\$4 adj2 layer\$2) and aperture and (di lectric adj2 mirr r)
2	BRS	5	laser and substrate and (epitaxial\$4 adj2 layer\$2) and aperture and (dielectric adj2 mirror) and (implanted adj2 (region or area))
3	BRS	0	skogman-richard.in.
4	BRS	24	skogman.in.
5	BRS	0	laser and substrate and (epitaxial\$4 adj2 layer\$2) and aperture and (dielectric adj2 mirror) and (implanted adj2 (region or area)) and ((partial or incomplete) adj3 dbr adj2 stack)
6	BRS	0	laser and substrate and (epitaxial\$4 adj2 layer\$2) and aperture and (dielectric adj2 mirror) and ((partial or incomplete) adj3 dbr adj2 stack)
7	BRS	2	5283447.pn.
8	BRS	5	laser and substrate and (epitaxial\$4 adj2 layer\$2) and aperture and (dielectric adj2 mirror) and (implanted adj2 (region or area)) and vcsel
9	BRS	2	laser and substrate and (epitaxial\$4 adj2 layer\$2) and aperture and (dielectric adj2 mirror) and (implanted adj2 (region or area)) and vcsel and ((reduce\$2 or lower\$2) adj2 resistance)
10	BRS	2	6031243.pn.
11	BRS	803	(dielectri adj2 mirror) and ((silic n adj dioxide) or (titanium dioxid ) or (silicon nitride))

	<b>DBs</b>	<b>Time Stamp</b>	<b>Comments</b>	<b>Error Definition</b>
<b>1</b>	<b>USPAT; US-P PUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 11:40</b>		
<b>2</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 12:16</b>		
<b>3</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 11:41</b>		
<b>4</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 11:41</b>		
<b>5</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 11:56</b>		
<b>6</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 11:56</b>		
<b>7</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 13:10</b>		
<b>8</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 12:17</b>		
<b>9</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 12:18</b>		
<b>10</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 13:16</b>		
<b>11</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 13:17</b>		

	Type	Hits	Search Text
12	BRS	60	(dielectric adj2 mirror) and ((silicon adj dioxide) or (titanium dioxide) or (silicon nitride)) and laser and vcsel
13	BRS	0	laser and (expitaxial\$4 adj2 layer\$2) and photoresist and aperture and (dielectric adj2 material) and (metal adj2 layer) and ((liftoff or lift-off) adj2 layer)
14	BRS	0	laser and (expitaxial\$4 adj2 layer\$2) and photoresist and aperture and (dielectric adj2 material) and (metal adj2 layer)
15	BRS	470	(method adj2 laser adj2 fabrication) or (method adj2 fabricating adj2 laser)
16	BRS	14	(method adj2 laser adj2 fabrication) or (method adj2 fabricating adj2 laser) and (photoresist or photo-resist) and (epitaxial\$4 adj2 layer\$2) and (metal adj2 layer\$2)
17	BRS	5	((method adj2 laser adj2 fabrication) or (method adj2 fabricating adj2 laser)) and (photoresist or photo-resist) and (epitaxial\$4 adj2 layer\$2) and (metal adj2 layer\$2)
18	BRS	4	((method adj2 laser adj2 fabrication) or (method adj2 fabricating adj2 laser)) and (photoresist or photo-resist) and (epitaxial\$4 adj2 layer\$2) and (metal adj2 layer\$2) and pattern\$4
19	BRS	0	((method adj2 laser adj2 fabrication) or (method adj2 fabricating adj2 laser)) and (photoresist or photo-resist) and (epitaxial\$4 adj2 layer\$2) and (metal adj2 layer\$2) and pattern\$4 and (implant\$4 adj2 region\$2)
20	BRS	0	((method adj2 laser adj2 fabrication) or (method adj2 fabricating adj2 laser)) and (photoresist r photo-resist) and (epitaxial\$4 adj2 layer\$2) and (metal adj2 layer\$2) and pattern\$4 and ((liftoff or lift-off) adj2 layer)

	<b>DBs</b>	<b>Time Stamp</b>	<b>C m m n t s</b>	<b>Error Definition</b>
<b>12</b>	<b>USPAT; US-P PUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 13:38</b>		
<b>13</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 13:41</b>		
<b>14</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 14:15</b>		
<b>15</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 14:18</b>		
<b>16</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 14:26</b>		
<b>17</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 14:28</b>		
<b>18</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 14:33</b>		
<b>19</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 14:32</b>		
<b>20</b>	<b>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB</b>	<b>2002/08/26 14:33</b>		